

IN THE CLAIMS

Please amend the claims as follows:

Claim 1 (Currently Amended): A processing device comprising:

a chamber  $[(12)]$  defining a processing area;

a mounting table  $[(16)]$ , disposed in the chamber  $[(12)]$ , for mounting thereon an object to be processed; and

a gas supply port  $[(19)]$  for supplying a gas into the chamber  $[(12)]$ , the gas supply port  $[(19)]$  being provided at a surface  $[(12b)]$  of the chamber  $[(12)]$ ; and

a shower head fitted in the gas supply port and having a plurality of gas supply openings at an its surface exposed to an inside of the chamber,

wherein the mounting table  $[(16)]$  is disposed substantially parallel to the surface  $[(12b)]$  of the chamber  $[(12)]$ ; and

in a substantially vertical cross section of the chamber  $[(12)]$  taken along a flow of the gas from the gas supply port  $[(19)]$  toward the object to be processed, a sidewall  $[(12d)]$  of the chamber  $[(12)]$  defining the processing area and abutting on the surface  $[(12b)]$  of the chamber forms an angle greater than  $90^\circ$  with the surface  $[(12b)]$  of the chamber and extends close to the mounting table;  $[(16)]$  and

the plurality of gas supply openings are provided substantially throughout the exposed surface of the shower head.

Claim 2 (Currently Amended): The processing device of claim 1, wherein the gas supply port  $[(19)]$  is configured to have a substantially same area as that of the object to be processed.

Claim 3 (Currently Amended): The processing device of claim 1, wherein in a substantially vertical cross section of the mounting table  $[(16)]$  taken along the flow of the gas from the gas supply port  $[(19)]$  toward the object to be processed, a mounting surface on which the object to be processed is mounted forms an angle greater than  $90^\circ$  with a side surface of the mounting table  $[(16)]$  abutting on the mounting surface.

Claim 4 (Currently Amended): The processing device of claim 3, wherein in a substantially vertical cross section of the chamber  $[(12)]$  and the mounting table  $[(16)]$  taken along the flow of the gas from the gas supply port  $[(19)]$  toward the object to be processed, the sidewall  $[(12d)]$  of the chamber is configured to be substantially parallel to the side surface of the mounting table  $[(16)]$ .

Claim 5 (Currently Amended): The processing device of claim 4, wherein in a substantially vertical cross section of the chamber  $[(12)]$  and the mounting table  $[(16)]$  taken along the flow of the gas from the gas supply port  $[(19)]$  toward the object to be processed, the distance between the sidewall  $[(12d)]$  of the chamber and the side surface of the mounting table  $[(16)]$  is set to be less than the distance between the surface  $[(12b)]$  of the chamber and the object to be processed.

Claim 6 (Currently Amended): A processing device comprising:  
a chamber  $[(12)]$  defining a processing area;  
a mounting table  $[(16)]$ , disposed in the chamber  $[(12)]$ , for mounting thereon an object to be processed; and  
a gas supply port  $[(19)]$  for supplying a gas into the chamber  $[(12)]$ , the gas supply port  $[(19)]$  being provided at a surface  $[(12b)]$  of the chamber  $[(12)]$ ;

wherein the mounting table  $[(16)]$  is disposed substantially parallel to a flow direction of the gas supplied from the gas supply port  $[(19)]$ ; and

in a substantially vertical cross section ~~and/or a substantially horizontal section~~ of the chamber  $[(12)]$ , a sidewall  $[(12d)]$  of the chamber  $[(12)]$  defining the processing area and abutting on the surface  $[(12b)]$  of the chamber forms an angle greater than  $90^\circ$  with the surface  $[(12b)]$  of the chamber and extends close to the mounting table;  $[(16)]$  and

the mounting table has a mounting surface for mounting thereon the object to be processed and a side surface forming an angle greater than  $90^\circ$  with the mounting surface.

Claim 7 (Currently Amended): A processing device comprising:

a chamber  $[(12)]$  defining a processing area;

a mounting table  $[(16)]$ , disposed in the chamber  $[(12)]$ , for mounting thereon an object to be processed;

a gas supply port  $[(19)]$  for supplying a gas into the chamber  $[(12)]$ , the gas supply port  $[(19)]$  being provided at a surface  $[(12b, 12a)]$  of the chamber  $[(12)]$ ; ~~and~~

a gas exhaust port  $[(13)]$  for evacuating the chamber  $[(12)]$ ; and

a shower head fitted in the gas supply port and having a plurality of gas supply openings at its surface exposed to an inside of the chamber,

wherein at least one of sidewalls  $[(12d, 12aa)]$  of the chamber  $[(12)]$  defining the processing area and abutting on one surface  $[(12b, 12a)]$  of the chamber  $[(12)]$  forms an angle greater than  $90^\circ$  with said one surface  $[(12b, 12a)]$  of the chamber  $[(12)]$  and extends close to at least a portion of an outer surface of the object to be processed;

the gas flows a flow passageway whose cross sectional area is gradually increased from the gas supply port  $[(19)]$  to a proximal end of the object to be processed and is

gradually decreased from a distal end of the object to be processed to the gas exhaust port;

[[ (13) ]] and

the plurality of gas supply openings are provided substantially throughout the exposed surface of the shower head.

Claims 8-9 (Canceled).

Claim 10 (Currently Amended): A processing device comprising:

a chamber [[ (12) ]] defining a processing area;

a mounting table [[ (16) ]], disposed in the chamber [[ (12) ]], for mounting thereon an object to be processed; and

a gas supply port [[ (19) ]] for supplying a gas into the chamber [[ (12) ]], the gas supply port [[ (19) ]] being provided at a surface [[ (12b) ]] of the chamber [[ (12) ]]; and

a shower head fitted in the gas supply port and having a plurality of gas supply openings at an its surface exposed to an inside of the chamber,

wherein in a substantially vertical cross section of the chamber [[ (12) ]] taken along a flow of the gas from the gas supply port [[ (19) ]] toward the object to be processed, a sidewall [[ (12d) ]] of the chamber [[ (12) ]] defining the processing area and abutting on the surface [[ (12b) ]] of the chamber extends slant at an angle greater than 90° with respect to the surface [[ (12b) ]] of the chamber to be close to the mounting table [[ (16) ]]; and

a side surface of the mounting table [[ (16) ]] is configured to match the slant of the sidewall; [[ (12d) ]] and

the plurality of gas supply openings are provided substantially throughout the exposed surface of the shower head.

Claim 11 (New): A processing device comprising:

a chamber defining a processing area;

a mounting table, disposed in the chamber, for mounting thereon an object to be processed; and

a gas supply port for supplying a gas into the chamber, the gas supply port being provided at a surface of the chamber;

wherein the mounting table is disposed substantially parallel to a flow direction of the gas supplied from the gas supply port; and

in a substantially horizontal section of the chamber, a sidewall of the chamber defining the processing area and abutting on the surface of the chamber forms an angle greater than 90° with the surface of the chamber and extends close to the mounting table.